

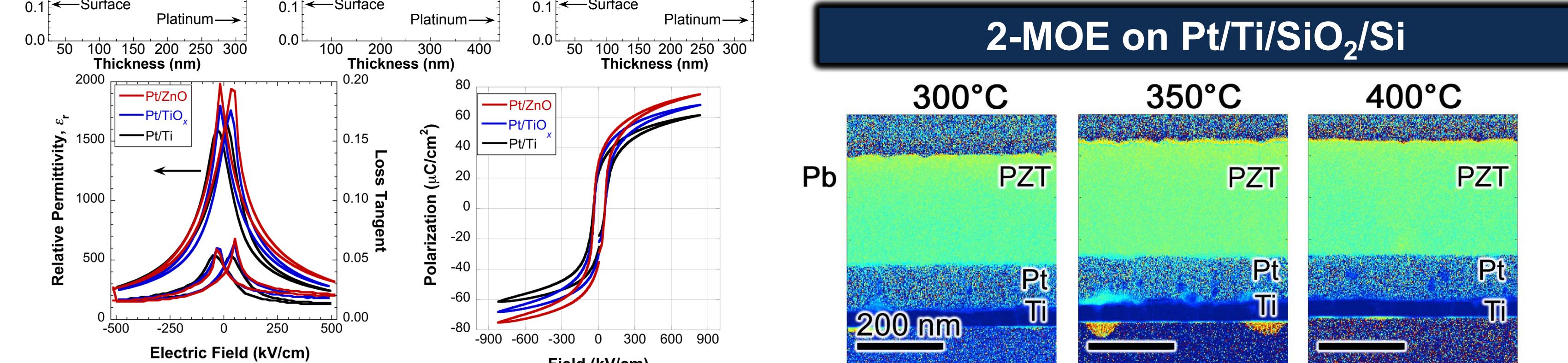
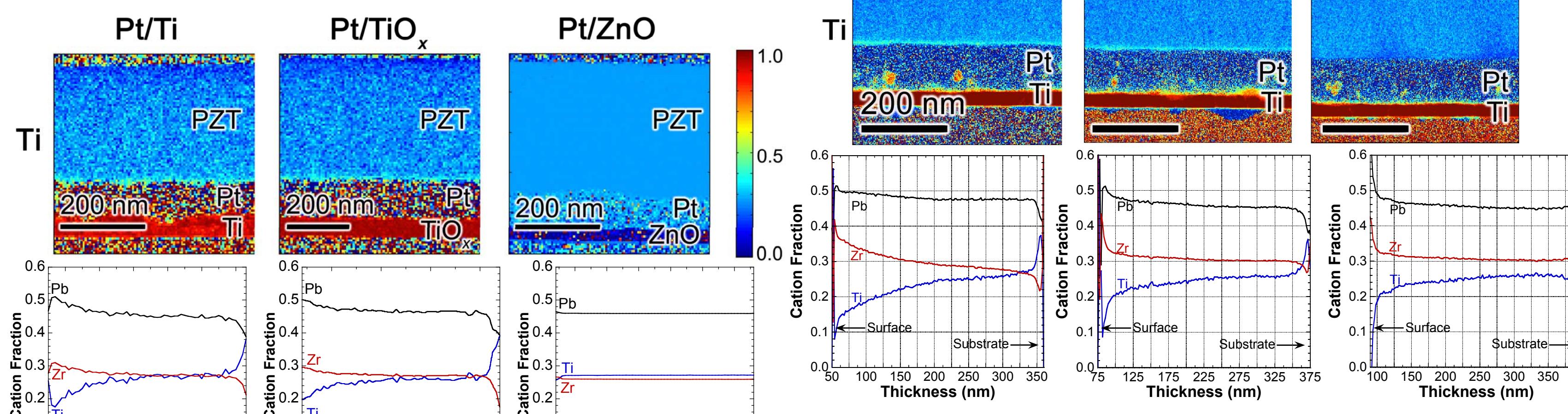
# Solution Chemistry, Substrate, and Processing Effects on the Chemical Heterogeneity in PZT Films

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## Motivation

Chemical heterogeneities in ferroelectrics have long been identified as a source of degraded ferroelectric, dielectric, and piezoelectric properties. This is particularly true for thin films where substrate sources of contamination can have substantially deleterious effects.

We previously identified a platinized silicon substrate stack, Pt/ZnO/SiO<sub>2</sub>/Si, that enables processing at temperatures of 900°C and eliminates diffusion of chemical species from the metallization adhesion layers. Our results indicated that chemical gradients do not form in solution derived PZT films without titanium in the metallization stack. This result is at odds with the many literature reports of chemical gradients in other PZT processing sequences.



## Goals

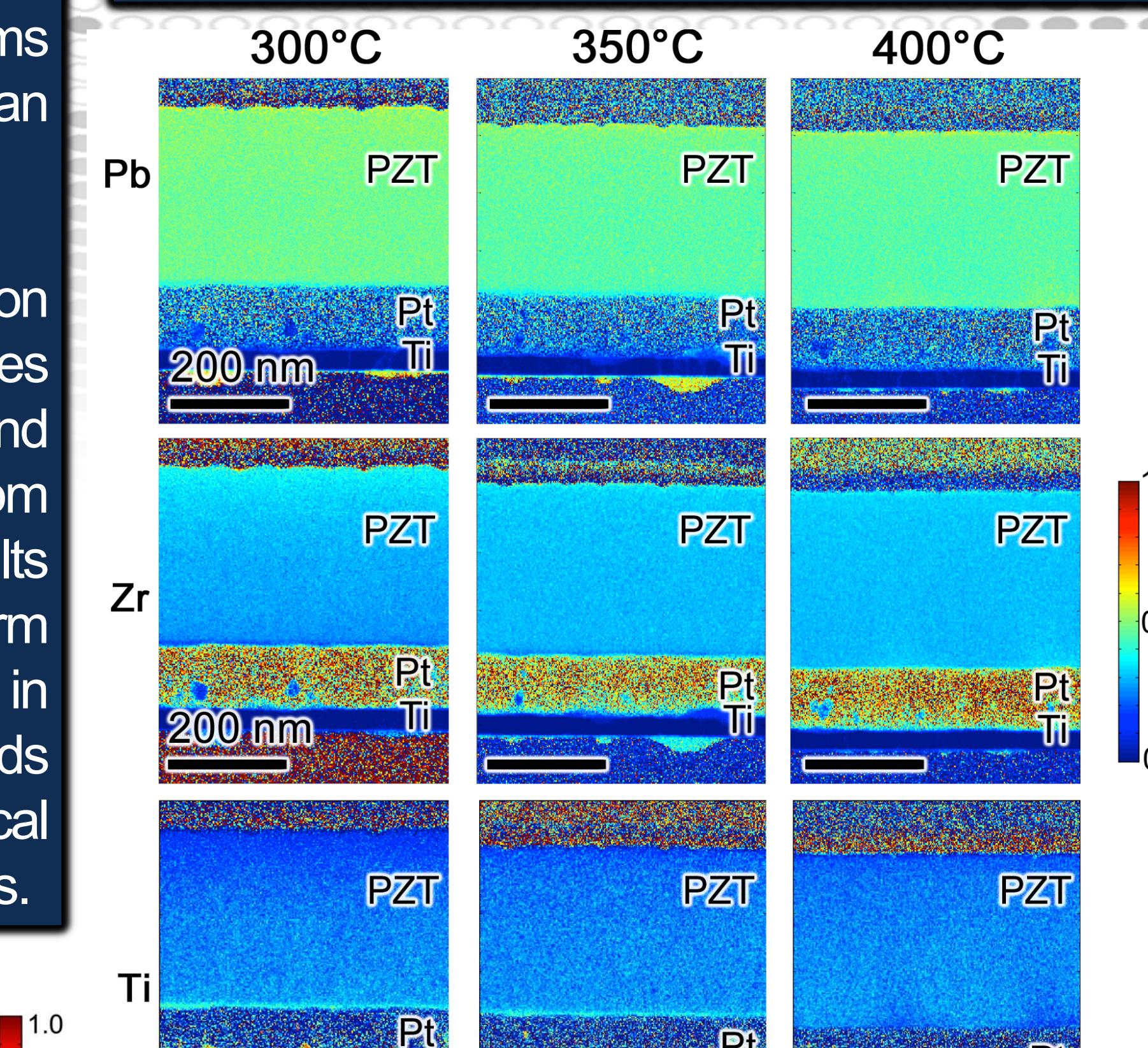
1. Determine if solution chemistry or pyrolysis condition have a role in gradient formation by comparing IMO and 2-MOE chemistries
2. Determine if the heating method and rate affects gradient formation on substrates devoid of titanium
3. Determine if there is a thermodynamic driving force for gradient formation

## Methodology

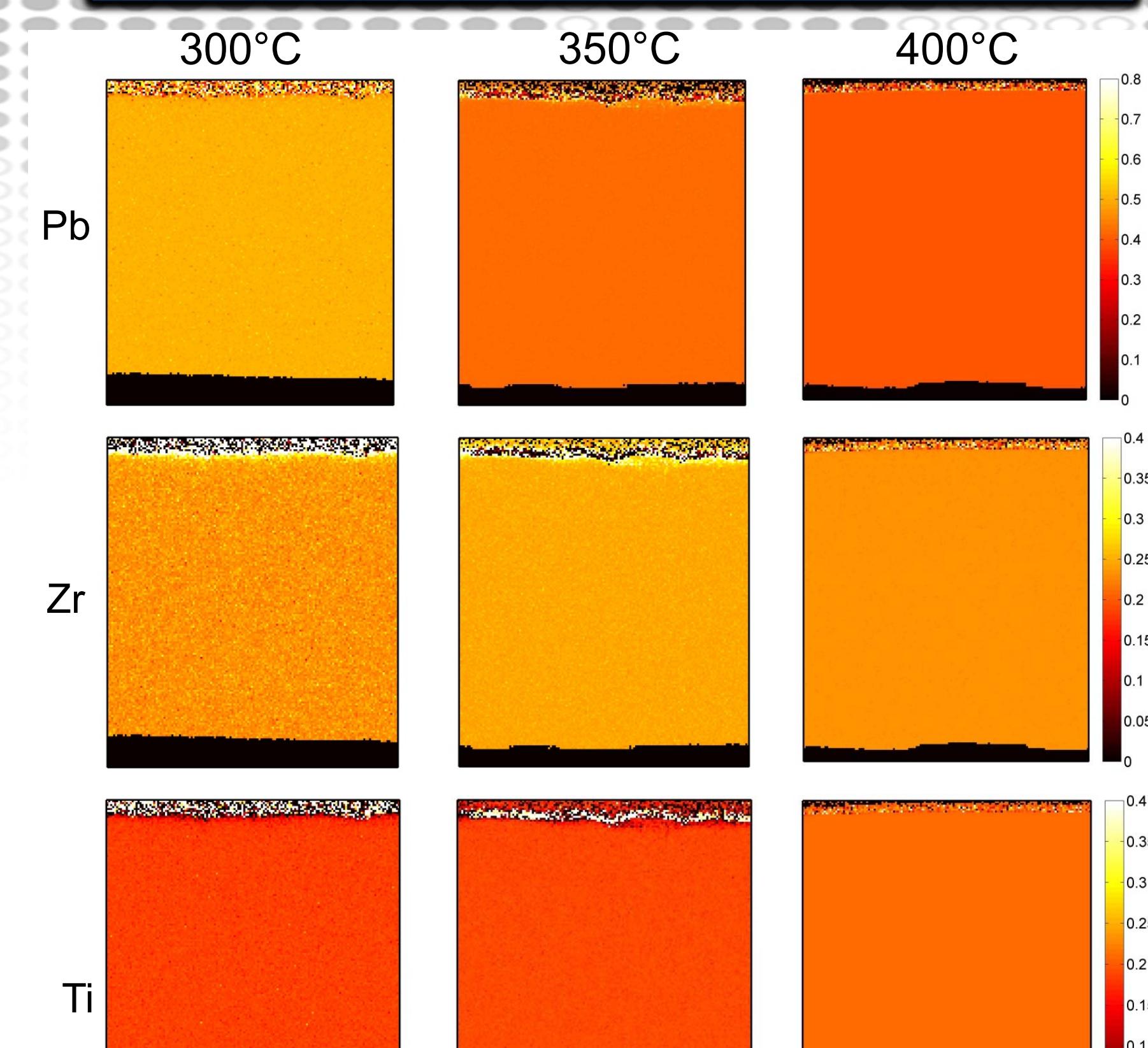
1. Compare IMO and 2-MOE-derived PZT on Pt/Ti and Pt/ZnO
2. Determine pyrolysis temperature effect: 300, 350, 400°C
3. Determine if the heating method and rate affects gradient formation on Pt/ZnO substrates: RTA vs Furnace

## Solution Chemistry and Pyrolysis Temperature Effects

### IMO on Pt/Ti/SiO<sub>2</sub>/Si

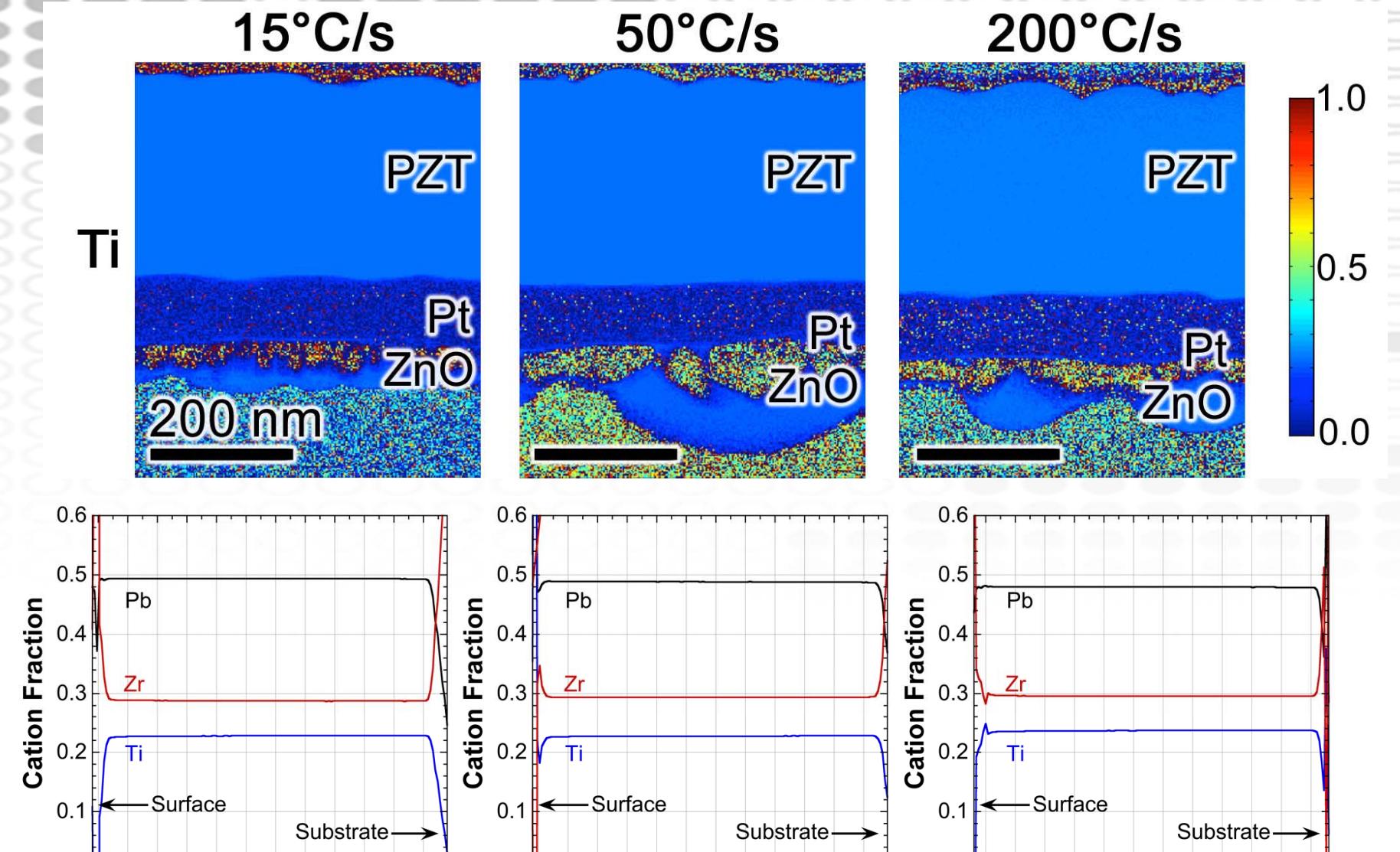


### IMO on Pt/ZnO/SiO<sub>2</sub>/Si



## Heating Rate Effects: RTA

### IMO on Pt/ZnO/SiO<sub>2</sub>/Si RTA



### 2-MOE on Pt/ZnO/SiO<sub>2</sub>/Si RTA

